

Software for nano/micro lithography

The software developed in Interface Ltd. can be used in microelectronic and nanotechnology industries and research centers for designing and producing modern micro- and nano-electronic devices.

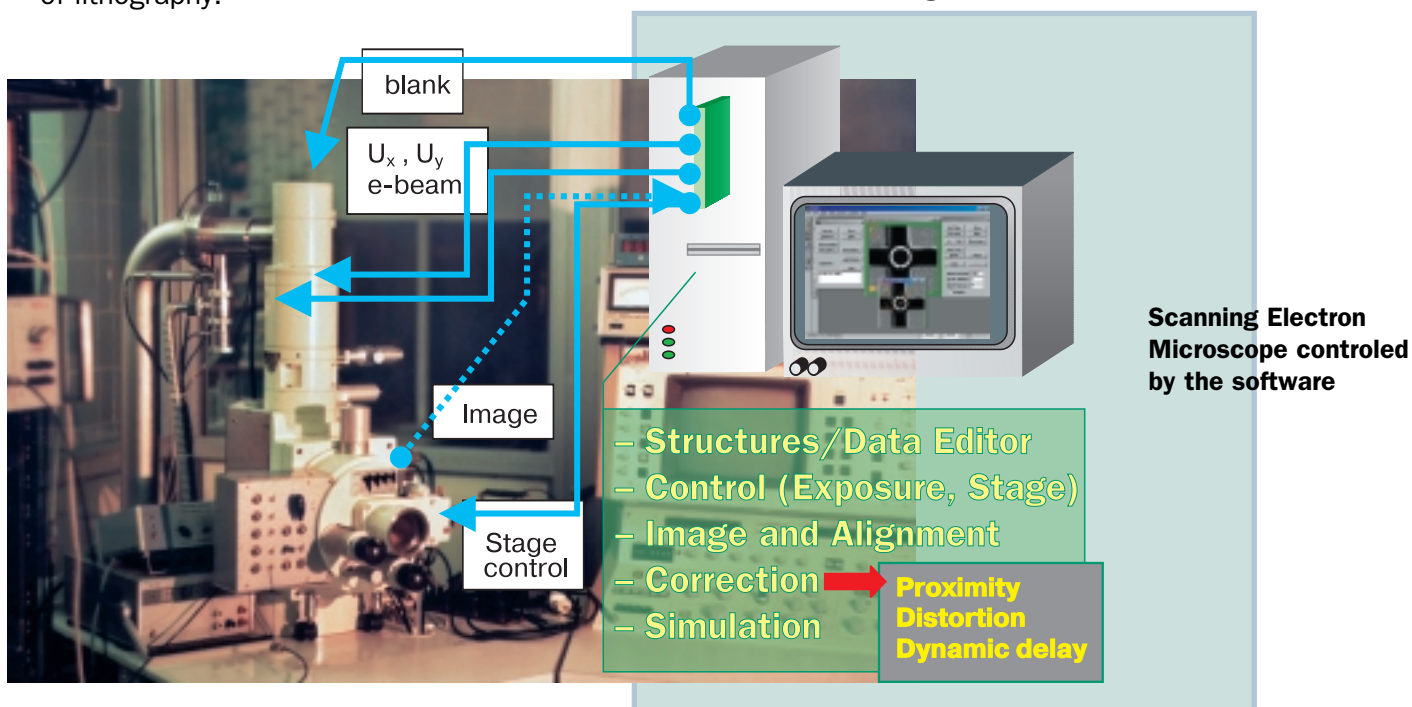
Purposes

- To obtain the ultimate lithography resolution for a technological and laboratory setup. To this end,
 - make correction for proximity effect during data preparation for lithography;
 - compensate for the distortion of a scanning system during exposure and image acquisition.
- To convert any scanning electron microscope (SEM) into an e-beam lithography.
- To predict results of lithography by simulating.
- To ensure adjustment for various configurations of lithographic equipment; for the presence or absence of beam blanking systems, stages, etc.
- To create three-dimensional structures in a resist.
- To familiarize user with the basic principles of lithography.

Description

The software package was developed to perform three basic functions:

- Data preparation for exposure (via Graphical Data Base).
- Manual input and transformation of data.
- The proximity effect correction.
- Modeling of exposure and resist development.
- Data import and export in various formats (GDSII, DXF, ELM...).
- Special transformation of data (Postprocessing, Group, Ungroup, Transformation, Modification, menu Edit) for selecting structure elements at boundaries (Frame), conversion of a positive image into a negative one (Negative), joining of elements (Union), etc.
- Exposure control
 - Variable exposure (dwell) times for proximity correction.
 - Synchronized movement of electron-beam and a stage.



- «On-the-fly» compensation of dynamic delays and distortion.
- Video control, system tuning.
- Alignment of successive lithographies via a set of marker windows.
- Digital microscope (a simple editor for creating a system of marker windows).
- System for acquisition of grayscale images.
- Procedures for the software adjustment to compensate the inaccuracies of a scanning system and a stage movement system.

Fields of application

- Microelectronics.
- Nanotechnology.
- 3D nano-micro structures (including biology).
- Diffractive optics (synthetic holograms) for visible and X-ray range.
- Digital microscopy.

Easy installed on

- SEMs and lithographs (JEOL, PHILIPPS, ZEISS, LEICA,..).
- Focused Ion Beam machines.
- STM/AFM's.

System requirements:

Windows NT, 2000, XP.

